

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	10085	(electrostatic near5 (chuck or position\$4 or stage or support\$4)) same (wafer or substrate or reticle or mask or pattern\$4 or object)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:17
L2	4642	1 and ((insulat\$4 or dielectric) near4 (layer or coat\$4 or surface))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:20
L3	109	2 and ((pin or protrusion or project\$6 or burl) near7 (conduction or conductive or metal) near5 (layer or coat\$4 or surface))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:47
L4	1	3 and (specific adj3 resistivity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:40
L5	32	3 and (resistivity)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:40
L6	2	"6754062"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/24 10:50
L7	17	"5777838"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/24 10:51
L8	1	((electrostatic near4 (chuck or stage or position\$4 or support\$4)) near6 (wafer or substrate or object or reticle or mask or target or pattern\$4)) and ((dielectric or insulation) near5 (layer or member or element or coat\$4 or surface)) and ((conductive or conduction or metal\$4) near5 (layer or surface or member or element) near5 (pin or protrusion or project\$4 or burl)) and (resistivity)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/24 10:57